



Electron Controlled Chemical Lithography

2010 Meeting

The third meeting of COST Action CM0601

**STERDYŃ, POLAND**

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**BOOK OF ABSTRACTS**



## **Dissociation cross sections for electron scattering on CF<sub>4</sub>**

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Carbon tetrafluoride, in argon discharge, is extensively used for etching in semiconductor industries. However, partial cross sections, in particularly for formation of radicals are poorly known. Furthermore, thresholds for formation of radicals are relatively high, what influences negatively etching patterns. Review of cross sections for carbon halides, gases potentially useful for chemical plasma etching, will be given.